

SOLAR InDop

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Inline doper with soft rollers

The InDop system applies a thin and homogeneous layer of phosphoric acid on the wafers before the inline diffusion process. The system offers optimal line integration with the RENA process equipment and automation thus simplifying the set-up of your front end. Using soft rollers to apply the phosphoric acid, it combines a robust process and low cost of ownership with an extremely gentle wafer transport system for highest mechanical and process yields.

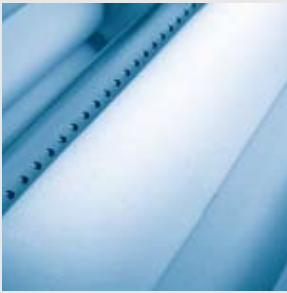
Areas of application

- Roll-on application of phosphoric acid for inline phosphorus diffusion
- Designed for multi- and monocrystalline wafers
- Automation systems available for loading and transfer to the inline furnace
 - with flip and buffer options

Features and benefits

- Ideal line integration with RENA InTex® systems
- Doping process adapted to the texture
- Double side coating for optimised P-gettering on both sides
- Low cost of ownership by using phosphoric acid as precursor
- Formation of a thin PSG layer, easy to remove
- Excellent process homogeneity
- Stable process control
- Online monitoring of the deposited phosphoric acid layer
- Best emitter profiles in combination with InOxSide® EB





Roll-on system



Roll-on system



Front view InDop

Technical Data InDop

InDop HT	
Platform	<p>NIAK</p> <p>5 lanes for 156 mm wafers</p>
Process	Deposition of phosphoric acid for inline phosphorus diffusion
Dimensions	3000 x 2150 x 2350 mm (length x width x height)
Throughput	<ul style="list-style-type: none"> • 1200 - 3600 wafers/h gross • wafer size 156 mm
Wafer thickness	> 150 µm